

**REMARKS**

The amendment is merely the incorporation of original claim 6 into original 1. Applicants submit that the amendment does not add any new matter to the disclosure.

Applicants hereby confirm the election of group I, claims 1-16 without traverse.

The invention centers on methods of locally altering a feature of an existing pattern. The invention achieves this result with minimal side reaction by use of a combination of local chemical delivery with activation energy provided by illumination.

Applicants submit that the rejections on the basis of obviousness-type double patenting over copending Application Nos. 10/261,275 and 10/604,486 and US Patents 6,787,783 and 6,730,237 are rendered moot in view of the incorporation of claim 6 into claim 1 since original claim 6 was not rejected on the basis of obviousness-type double patenting.

Applicants submit that the rejections the basis of anticipation 35 USC 102(b) in view of US Patent 5,851,413 (Casella et al.); the "Dip Pen..." article of Ivanisevic et al.; US Patent 5,055,696 (Haraichi et al.) are rendered moot in view of the incorporation of claim 6 into claim 1 since original claim 6 was not rejected over those references.

Yamaguchi et al. (US 2003/0003393 A1) discloses a photoresist composition and methods for making photoresist patterns. The methods of Yamaguchi et al. involve the global application of a photoresist layer on a

substrate followed by patterned exposure to an imaging radiation to create a photoresist pattern. In example 1, Yamaguchi et al. disclose application of a photoresist layer over a chrome layer on a glass substrate. The photoresist layer is then exposed to light through a near field probe 104. Once the desired photoresist pattern is formed, then the pattern is transferred to the chrome layer by etching. Yamaguchi et al. does not disclose or suggest the local delivery of chemicals to an existing pattern. Yamaguchi et al. does not disclose or suggest the alteration of a feature of an existing pattern by the chemical reaction.

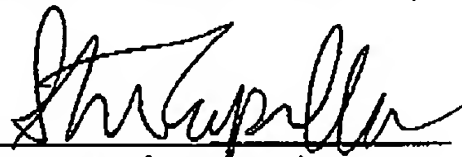
Martin et al. discloses illumination of a probe tip to create photon scattering. It is not apparent that the combination of Martin et al. with Yamaguchi et al. would result in a workable process in as much as Yamaguchi et al. is seeking to generate radiation of specific wavelengths. Also, photon scattering would not be desirable in the process of Yamaguchi et al. where the radiation must be provided in a precise pattern. The combination of Martin et al. with Yamaguchi et al. would still not result in the local delivery of chemical or the alteration of an existing pattern by chemical reaction.

West is recited to show the imparting of thermal energy by absorption of scattered photons. It is not apparent that the combination of West with Yamaguchi et al. would result in a workable process in as much as thermal heating would not be desirable in the process of Yamaguchi et al. where the energy must be provided in a precise pattern. The combination of West with Yamaguchi et al. would still not result in the local delivery of chemical or the alteration of an existing pattern by chemical reaction.

For the above reasons, applicants submit that the claims are patentable and that the application is in condition for allowance. Such allowance is earnestly and respectfully solicited.

Respectfully submitted,

Hendrik F. Hamann et al.

By   
Steven Capella, Attorney  
Reg. No. 33,086  
Telephone: 845-894-3669